ELSEVIER

Thin Solid Films 296 (1997) 189

thin solid films

Author Index of Volume 296

Abrutis, A., 79
Achiq, A., 15
Adriaenssens, G.J., 118
Akasaka, T., 2
Albrecht, M., 49
Alessandri, M., 91
Andrei, A., 23
Anton, R., 69
Apte, R.B., 172
Arai, T., 19
Armstrong, B.M., 7, 141
Azuma, K., 72

Baev, A.A., 184
Baine, P.T., 7, 141
Bakin, A.S., 168
Baumgärtner, H., 37
Ben Chaabane, R., 145, 148
Bergmann, R.B., 49
Bertrand, N., 66
Bestaev, M.V., 168
Bogdanov, P.A., 41
Boher, P., 53
Bonnaud, O., 53, 133
Boreli, F., 181
Borghesi, A., 91
Brenot, R., 94
Briand, D., 53
Bulkin, P., 66

Canet, P., 114
Canut, B., 32
Carchano, H., 114
Carlotti, G., 102
Carluccio, R., 57
Carmo, M.C., 126
Cerqueira, M.F., 118, 126
Chanelière, Ch., 32
Chitica, N., 23
Cina, S., 57
Cornet, A., 177
Cruz, J., 110

Dayoub, F., 137
Deimel, P.P., 157
De Leuw, M.C.V., 152
Dimitrov, D.Tz., 168
Dinescu, G., 23
Dinescu, M., 23
Dorfman, S., 76
Doucet, L., 102
Drevillon, B., 66, 94
Drüsedau, T.P., 69
Dubois, Ch., 32
Dupeux, M., 102

Eisele, I., 37
El Beqqali, O., 148
El-Hdiy, A., 106

Fantoni, A., 110, 164
Felten, F., 79
Ferrari, A., 23
Ferreira, J.A., 118, 126
Ferroni, G., 91
Fortin, B., 53
Fortunato, G., 57, 82
French, I., 94
Friligkos, S., 57
Fuks, D., 76
Furtsch, M., 177

Gagić, V., 44
Gamble, H.S., 7, 141
Gamoudi, M., 145, 148
Garrido, B., 98
Gartner, M., 23
Giardini, M.E., 91
Gourbilleau, F., 15
Grabolla, T., 37
Guillaud, G., 145, 148
Gurlo, A.Ch., 41

Hamma, S., 11
Hansch, W., 37
He, D., 2
Heifets, E., 76
Hellmich, W., 157
Holleman, J., 152

Ivanovskaya, M.I., 41

Jackson, W.B., 172
Jansen, J., 118
John, T.-M., 69
Jourdain, M., 106

Karanović, L., 44
Kis-Sion, K., 53, 133
Kitazawa, N., 2
Kleider, J.P., 137
Koopmans, B., 49
Kotomin, E., 76
Kouchi, T., 72
Koynov, S., 164
Krinke, J., 49
Kuo, Y., 28

Labeau, M., 79
Lalande, F., 114
La Monica, S., 23
Laugier, A., 32
Lebihan, F., 53
Lebrun, H., 129
Lee, B., 7, 141
Lemiti, M., 32
Lioutas, Ch.B., 28
Lollman, D., 114
López, M., 98

Madelon, R., 15
Maiello, G., 23
Marazzi, M., 91
Martin, S., 129
Martinez, A., 122
Martins, R., 110
Masini, G., 23
Meinertzhagen, A., 106
Mencaraglia, D., 137
Milošević, O., 44
Mitchell, S.J.N., 7, 141
Mitrović, A., 44
Miyamoto, Y., 2
Mohammed-Brahim, T., 53, 133
Moore, A., 172
Morante, J.R., 98, 177
Moreno, J.A., 98
Moshnikov, V.A., 168
Mottet, S., 129
Mourgues, K., 133
Müller, G., 157

Nguyen, M., 172
Novković, D., 181
Nylen, P., 172

Offenberg, M., 177
Orlik, D.R., 41
Osmokrović, P., 181

Paloura, E.C., 28
Pesty, O., 114
Pichon, L., 133
Proverbio, E., 23

Quinn, L.J., 7, 141

Ramgopal Rao, V., 37
Raoult, F., 133
Ready, S.E., 172
Rem, J.B., 152
Remaki, B., 148
Richards, B., 49
Rizk, R., 15
Robertson, J., 61
Roca i Cabarrocas, P., 11, 94
Rolland, A., 129
Romanovskaya, V.V., 41
Ryabtsev, S.V., 184

Salace, G., 106
Samitier, J., 98
Sandu, V., 23
Santos, P.V., 49
Sarrabayrouse, G., 122
Sarret, M., 53
Sassella, A., 91
Scheid, E., 98
Schwarz, R., 164
Semmache, B., 32
Sénateur, J.P., 79
Sharma, D.K., 37
Shimizu, I., 2
Shirai, H., 19, 72
Sibai, A., 32
Stehle, J.L., 53
Stehle, M., 53
Stoemenos, J., 57
Stojanović, B., 44
Stojanović, M., 181
Street, R.A., 172
Szydlo, N., 129

Tadeev, A.V., 184
Tairov, Yu.M., 168
Tandia A, A., 122
Toet, D., 49
Tutov, E.A., 184

Vanderhaghen, R., 94
Vasi, J., 37
Veit, P., 69
Ventura, P.J., 126
Verweij, J.F., 152
Vieira, M., 110, 164
Vilá, A., 98, 177
Vodnik, J., 44
Voivenel, P., 15
Vouroutzis, N., 28
Vuillaume, D., 106

Wagner, C., 157
Webb, R., 181
Weisfield, R.L., 172

Yu-Zhang, K., 79

Živković, L., 44

Elsevier Science S.A.

ELSEVIER

Thin Solid Films 296 (1997) 191–194

thin solid films

Subject Index of Volume 296

Aerosol spray pyrolysis
synthesis and deposition of ZnO based particles by aerosol spray pyrolysis, 44
Alpha spectrometry
characteristics of large area silicon surface barrier detectors, 181
Amorphous hydrogenated silicon carbide
capacity coupled r.f. discharge plasma jet treatment of a-SiC:H structures, 23
Amorphous materials
furnace and rapid thermal crystallization of amorphous Ge_xSi_{1-x} and Si for thin film transistors, 152
Amorphous substrate
early stages of microcrystalline silicon film growth on amorphous substrate with SiH_4 gas heating, 19
Annealing
structure and photoluminescence of annealed semi-insulating polycrystalline silicon material obtained by disilane, 98
investigation of the electrical properties of the metal–calixarene–semiconductor structures, 148
SnO_2 based gas sensitive sensor, 168
Atomic force microscopy
single shot excimer laser crystallization of silicon films deposited by LPCVD, 53
early stage growth of hydrogenated amorphous carbon, 72
Atomic hydrogen
growth of polycrystalline silicon thin films on glass, 2
Atomic scale
the Si/SiO_2 interface morphology study by molecular simulation, 122
Atomistic simulation
atomistic simulation of the [001] surface structure in $BaTiO_3$, 76

Carbon cathodes
amorphous carbon cathodes for field emission display, 61
Carbon etch stop
single crystal silicon on glass, 141
Cathode heating technique
early stages of microcrystalline silicon film growth on amorphous substrate with SiH_4 gas heating, 19
Charge trapping
charge trapping behaviour in deposited and grown thin metal–oxide–semiconductor gate dielectrics, 37
Chemical vapour deposition
elastic properties of silicon dioxide films deposited by chemical vapour deposition from tetraethylorthosilicate, 102
Circuit application
polycrystalline silicon thin-film transistors: A continuous evolving technology, 82
Crystalline orientation
the Si/SiO_2 interface morphology study by molecular simulation, 122
Crystallinity
early stages of microcrystalline silicon film growth on amorphous substrate with SiH_4 gas heating, 19
Crystallization
large area polycrystalline silicon thin films grown by laser-induced nucleation and solid phase crystallization, 49
furnace and rapid thermal crystallization of amorphous Ge_xSi_{1-x} and Si for thin film transistors, 152

Defects
stress field polarity effect on defects generation in thin silicon dioxide films, 106
Deposition
silicon nitride and oxynitride deposition by RT-LPCVD, 32
synthesis and deposition of ZnO based particles by aerosol spray pyrolysis, 44
deposition of SiO_2 in integrated distributed electron cyclotron resonance microwave reactor, 66
Diamond
amorphous carbon cathodes for field emission display, 61
Diamond-like carbon
amorphous carbon cathodes for field emission display, 61
Disilane
structure and photoluminescence of annealed semi-insulating polycrystalline silicon material obtained by disilane, 98
Document imaging
amorphous silicon sensor arrays for X-ray and document imaging, 172
Doping
optical properties of polycrystalline silicon thin films deposited by single-wafer chemical vapor deposition, 91

Elastic properties
elastic properties of silicon dioxide films deposited by chemical vapour deposition from tetraethylorthosilicate, 102
Electrical instabilities
polycrystalline silicon thin-film transistors: A continuous evolving technology, 82
Electrical properties
growth control and properties of microcrystallized silicon films deposited by hydrogen plasma sputtering, 15
study of the electrical properties of thin film transistors based on nickel phthalocyanine, 145
investigation of the electrical properties of the metal–calixarene–semiconductor structures, 148
Electrical properties and measurements
electrical and photoelectrical characterization of $GaAs_xS_y$ polycrystalline thin films, 114
Electron cyclotron resonance
deposition of SiO_2 in integrated distributed electron cyclotron resonance microwave reactor, 66
Electron diffraction
electron beam induced damage in N-rich SiN_x films deposited by plasma enhanced chemical vapour deposition, 28
Electron microscopy
large area polycrystalline silicon thin films grown by laser-induced nucleation and solid phase crystallization, 49

Elsevier Science S.A.

Electrostatic bonding
single crystal silicon on glass, 141

Ferroelectrics
atomistic simulation of the [001] surface structure in $BaTiO_3$, 76
Field emission display
amorphous carbon cathodes for field emission display, 61
Field polarity
stress field polarity effect on defects generation in thin silicon dioxide films, 106
Flat panel displays
low temperature (≤ 600 °C) unhydrogenated in-situ doped polysilicon thin film transistors: Towards a technology for flat panel displays, 133
Fluorine
deposition and characterisation of silicon grown in a $SiF_4/SiH_4/H_2$ mixture for TFT applications, 7

$GaAs_xS_y$
electrical and photoelectrical characterization of $GaAs_xS_y$ polycrystalline thin films, 114
Gas sensitivity
functional applications of large-area heterostructures of monocrystalline silicon-disordered semiconductors, 184
Gas sensors
SnO_2 based gas sensitive sensor, 168
Gate dielectrics
charge trapping behaviour in deposited and grown thin metal–oxide–semiconductor gate dielectrics, 37
Germanium
furnace and rapid thermal crystallization of amorphous Ge_xSi_{1-x} and Si for thin film transistors, 152
Germanium nanocrystals
germanium–carbon multilayer films prepared by magnetron sputtering—structure and thermally induced formation of Ge-nanocrystals, 69
Grain size
structure of poly-Si films obtained by laser annealing, 57
Growth
early stage growth of hydrogenated amorphous carbon, 72
Growth control
growth control and properties of microcrystallized silicon films deposited by hydrogen plasma sputtering, 15

Hall mobility measurements
single shot excimer laser crystallization of silicon films deposited by LPCVD, 53
Heterostructures
functional applications of large-area heterostructures of monocrystalline silicon-disordered semiconductors, 184
Hydrogen
long range effects of hydrogen during microcrystalline silicon growth, 11
Hydrogenated amorphous carbon
early stage growth of hydrogenated amorphous carbon, 72
Hydrogenated silicon
modelling a μc-Si:H p–i–n device under non-uniform illumination, 110
optical modulation spectroscopy of hydrogenated microcrystalline silicon, 118
wide spectral response in μc-Si:H photodiodes, 164
Hydrogen plasma sputtering
growth control and properties of microcrystallized silicon films deposited by hydrogen plasma sputtering, 15

Injection MOCVD
deposition of Ta_2O_5/SiO_2 multilayer films by a new process "injection MOCVD", 79
Interface morphology
the Si/SiO_2 interface morphology study by molecular simulation, 122
Interface states
comparison of Al/SiN/a-Si:H and Al/SiO_2/a-Si:H top gate structures under thermal bias stresses, 137

Laser annealing
structure of poly-Si films obtained by laser annealing, 57
Low pressure chemical vapour deposition
single shot excimer laser crystallization of silicon films deposited by LPCVD, 53
Low pressure rapid thermal chemical vapour deposition
silicon nitride and oxynitride deposition by RT-LPCVD, 32

Magnetron sputtering
germanium–carbon multilayer films prepared by magnetron sputtering—structure and thermally induced formation of Ge-nanocrystals, 69
Metal–calixarene–semiconductor structures
investigation of the electrical properties of the metal–calixarene–semiconductor structures, 148
Microcrystalline silicon
long range effects of hydrogen during microcrystalline silicon growth, 11
photoluminescence and structure properties from μc-Si:H and μc-Si:H-PS samples, 126
Microwave reflectivity
time resolved microwave conductivity measurements for the characterization of transport properties in thin film micro-crystalline silicon, 94
MIS structures
comparison of Al/SiN/a-Si:H and Al/SiO_2/a-Si:H top gate structures under thermal bias stresses, 137
Molecular simulation
the Si/SiO_2 interface morphology study by molecular simulation, 122
Molybdenum
electrical and photoelectrical characterization of $GaAs_xS_y$ polycrystalline thin films, 114
Multilayers
deposition of Ta_2O_5/SiO_2 multilayer films by a new process "injection MOCVD", 79

Nickel phthalocyanine
study of the electrical properties of thin film transistors based on nickel phthalocyanine, 145
Noise performance
polycrystalline silicon thin-film transistors: A continuous evolving technology, 82
Nuclear physics
characteristics of large area silicon surface barrier detectors, 181

Optical modulation spectroscopy
optical modulation spectroscopy of hydrogenated microcrystalline silicon, 118
Optical properties
growth control and properties of microcrystallized silicon films deposited by hydrogen plasma sputtering, 15
large area polycrystalline silicon thin films grown by laser-induced nucleation and solid phase crystallization, 49
deposition of SiO_2 in integrated distributed electron cyclotron resonance microwave reactor, 66
optical properties of polycrystalline silicon thin films deposited by single-wafer chemical vapor deposition, 91
Optoelectronics
sensor fabrication using thin film-on-silicon approaches, 157
Oxynitride
silicon nitride and oxynitride deposition by RT-LPCVD, 32

Photodiodes
wide spectral response in μc-Si:H photodiodes, 164
Photoluminescence
structure and photoluminescence of annealed semi-insulating polycrystalline silicon material obtained by disilane, 98
photoluminescence and structure properties from μc-Si:H and μc-Si:H-PS samples, 126
p–i–n devices
modelling a μc-Si:H p–i–n device under non-uniform illumination, 110
Plasma enhanced CVD
electron beam induced damage in N-rich SiN_x films deposited by plasma enhanced chemical vapour deposition, 28
deposition of SiO_2 in integrated distributed electron cyclotron resonance microwave reactor, 66
Plasma-enhanced (PE)-CVD
growth of polycrystalline silicon thin films on glass, 2
Plasma jets
capacity coupled r.f. discharge plasma jet treatment of a-SiC:H structures, 23
Polycrystalline silicon
growth of polycrystalline silicon thin films on glass, 2
Polysilicon
deposition and characterisation of silicon grown in a $SiF_4/SiH_4/H_2$ mixture for TFT applications, 7
texture and stress profile in thick polysilicon films suitable for fabrication of microstructures, 177
Poly-silicon films
structure of poly-Si films obtained by laser annealing, 57
Polysilicon thin films
low temperature (≤ 600 °C) unhydrogenated in-situ doped polysilicon thin film transistors: Towards a technology for flat panel displays, 133
Porosity
long range effects of hydrogen during microcrystalline silicon growth, 11
Porous silicon
photoluminescence and structure properties from μc-Si:H and μc-Si:H-PS samples, 126
Properties
photoluminescence and structure properties from μc-Si:H and μc-Si:H-PS samples, 126

Quasistatic capacitance
comparison of Al/SiN/a-Si:H and Al/SiO_2/a-Si:H top gate structures under thermal bias stresses, 137

μ-Raman
texture and stress profile in thick polysilicon films suitable for fabrication of microstructures, 177
Resistance evaluation
2D numerical simulation of a-Si:H TFTS: Application to parasitic contact resistances evaluation, 129

Semiconductors
capacity coupled r.f. discharge plasma jet treatment of a-SiC:H structures, 23
Sensor
structure and properties of sol–gel obtained SnO_2 and SnO_2–Pd films, 41
Sensor arrays
amorphous silicon sensor arrays for X-ray and document imaging, 172
Sensor fabrication
sensor fabrication using thin film-on-silicon approaches, 157
Silicon
large area polycrystalline silicon thin films grown by laser-induced nucleation and solid phase crystallization, 49
furnace and rapid thermal crystallization of amorphous Ge_xSi_{1-x} and Si for thin film transistors, 152
Silicon dioxide
deposition of Ta_2O_5/SiO_2 multilayer films by a new process "injection MOCVD", 79
stress field polarity effect on defects generation in thin silicon dioxide films, 106
comparison of Al/SiN/a-Si:H and Al/SiO_2/a-Si:H top gate structures under thermal bias stresses, 137
Silicon dioxide films
elastic properties of silicon dioxide films deposited by chemical vapour deposition from tetraethylorthosilicate, 102
Silicon-disordered semiconductors
functional applications of large-area heterostructures of monocrystalline silicon-disordered semiconductors, 184
Silicon nitride
silicon nitride and oxynitride deposition by RT-LPCVD, 32
comparison of Al/SiN/a-Si:H and Al/SiO_2/a-Si:H top gate structures under thermal bias stresses, 137
Silicon surface barrier detectors
characteristics of large area silicon surface barrier detectors, 181
Silicon wafers
sensor fabrication using thin film-on-silicon approaches, 157
Single-wafer chemical vapour deposition
optical properties of polycrystalline silicon thin films deposited by single-wafer chemical vapor deposition, 91
Sol
structure and properties of sol–gel obtained SnO_2 and SnO_2–Pd films, 41
Spectral response
wide spectral response in μc-Si:H photodiodes, 164
Spectroscopic ellipsometry
growth of polycrystalline silicon thin films on glass, 2
long range effects of hydrogen during microcrystalline silicon growth, 11
Sputtering
electrical and photoelectrical characterization of $GaAs_xS_y$ polycrystalline thin films, 114
Stress
stress field polarity effect on defects generation in thin silicon dioxide films, 106
texture and stress profile in thick polysilicon films suitable for fabrication of microstructures, 177
Surface relaxation
atomistic simulation of the [001] surface structure in $BaTiO_3$, 76
Synthesis
synthesis and deposition of ZnO based particles by aerosol spray pyrolysis, 44

Tantalum pentoxide
deposition of Ta_2O_5/SiO_2 multilayer films by a new process "injection MOCVD", 79
TEM
texture and stress profile in thick polysilicon films suitable for fabrication of microstructures, 177
Tetraethylorthosilicate
elastic properties of silicon dioxide films deposited by chemical vapour deposition from tetraethylorthosilicate, 102
Texture
texture and stress profile in thick polysilicon films suitable for fabrication of microstructures, 177
Thermal bias annealing
comparison of Al/SiN/a-Si:H and Al/SiO_2/a-Si:H top gate structures under thermal bias stresses, 137
Thermal vacuum deposition
SnO_2 based gas sensitive sensor, 168

Thin film
structure and properties of sol–gel obtained SnO_2 and SnO_2–Pd films, 41
Thin film transistor
deposition and characterisation of silicon grown in a $SiF_4/SiH_4/H_2$ mixture for TFT applications, 7
Thin film transistors
single crystal silicon on glass, 141
study of the electrical properties of thin film transistors based on nickel phthalocyanine, 145
Time resolved microwave conductivity
time resolved microwave conductivity measurements for the characterization of transport properties in thin film micro-crystalline silicon, 94
Tin dioxide
structure and properties of sol–gel obtained SnO_2 and SnO_2–Pd films, 41
SnO_2 based gas sensitive sensor, 168
Transistors
2D numerical simulation of a-Si:H TFTS: Application to parasitic contact resistances evaluation, 129
low temperature (≤ 600 °C) unhydrogenated in-situ doped polysilicon thin film transistors: Towards a technology for flat panel displays, 133
Transmission electron microscopy
electron beam induced damage in N-rich SiN_x films deposited by plasma enhanced chemical vapour deposition, 28
structure of poly-Si films obtained by laser annealing, 57
Transport properties
time resolved microwave conductivity measurements for the characterization of transport properties in thin film micro-crystalline silicon, 94

X-ray diffraction
single shot excimer laser crystallization of silicon films deposited by LPCVD, 53
texture and stress profile in thick polysilicon films suitable for fabrication of microstructures, 177
X-ray imaging
amorphous silicon sensor arrays for X-ray and document imaging, 172